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APPLICATION DATA SHEET**Application Information**

Application Type:: regular
Subject Matter:: utility
Title:: POSITIVE PHOTORESIST COMPOSITION AND
METHOD OF FORMING RESIST PATTERN
Attorney Docket Number:: SHIGA7.041APC

Inventor Information

Applicant Authority Type:: inventor
Primary Citizenship Country:: Japan
Status:: full capacity
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Inventor Information

Applicant Authority Type:: inventor
Primary Citizenship Country:: Japan
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Representative Information

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Domestic Priority Information

Application::	Continuity Type::	Parent Application::	Parent Filing Date::
This Application	National Phase	PCT/JP2004/010434	July 15, 2004

Foreign Priority Information

Country::	Application Number::	Filing Date::	Priority Claimed::
Japan	2003-275051	July 16, 2003	Yes

Assignment Information

Assignee Name:: TOKYO OHKA KOGYO, CO., LTD.

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